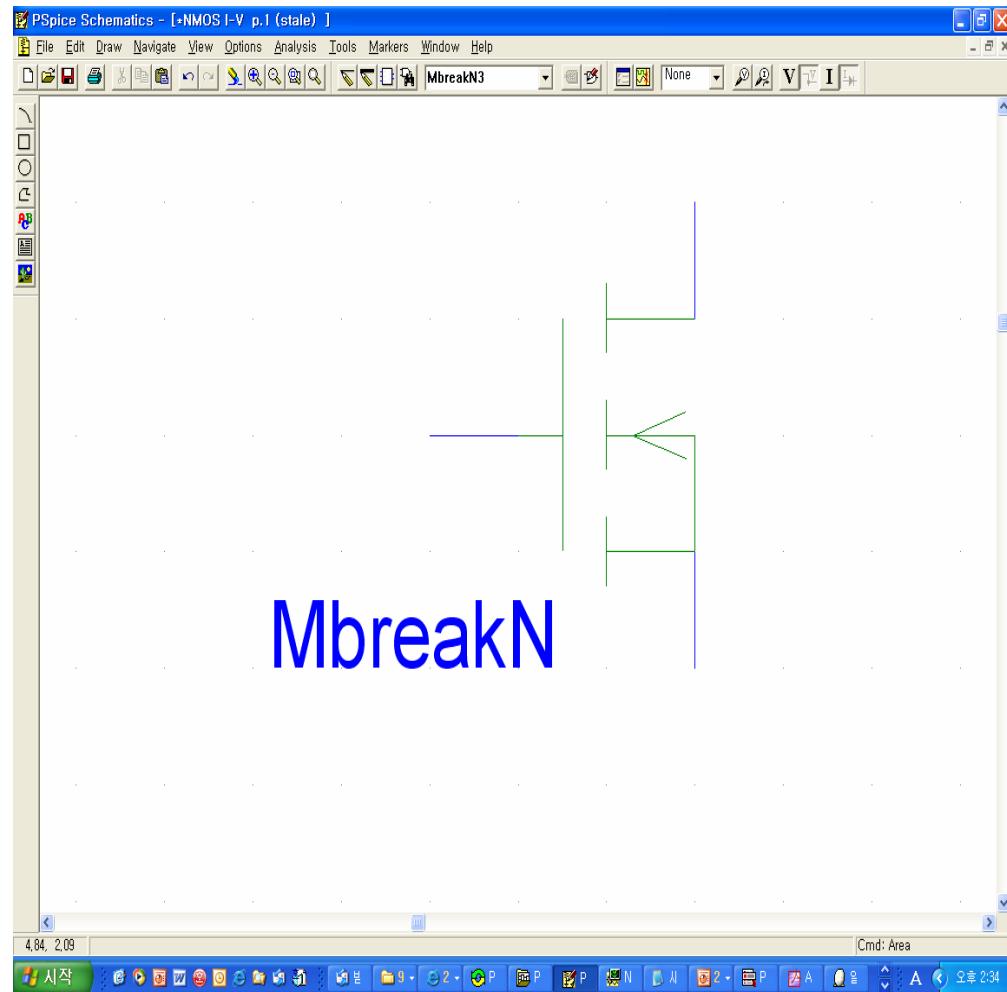
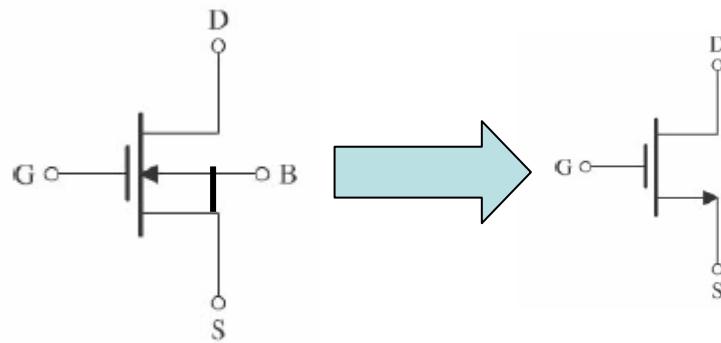


Lect. 8: MOSFET Simulation

PSPICE simulation of NMOS

1. Use **MbreakN3** model in PSPICE
(S and B are tied)



Lect. 8: MOSFET Simulation

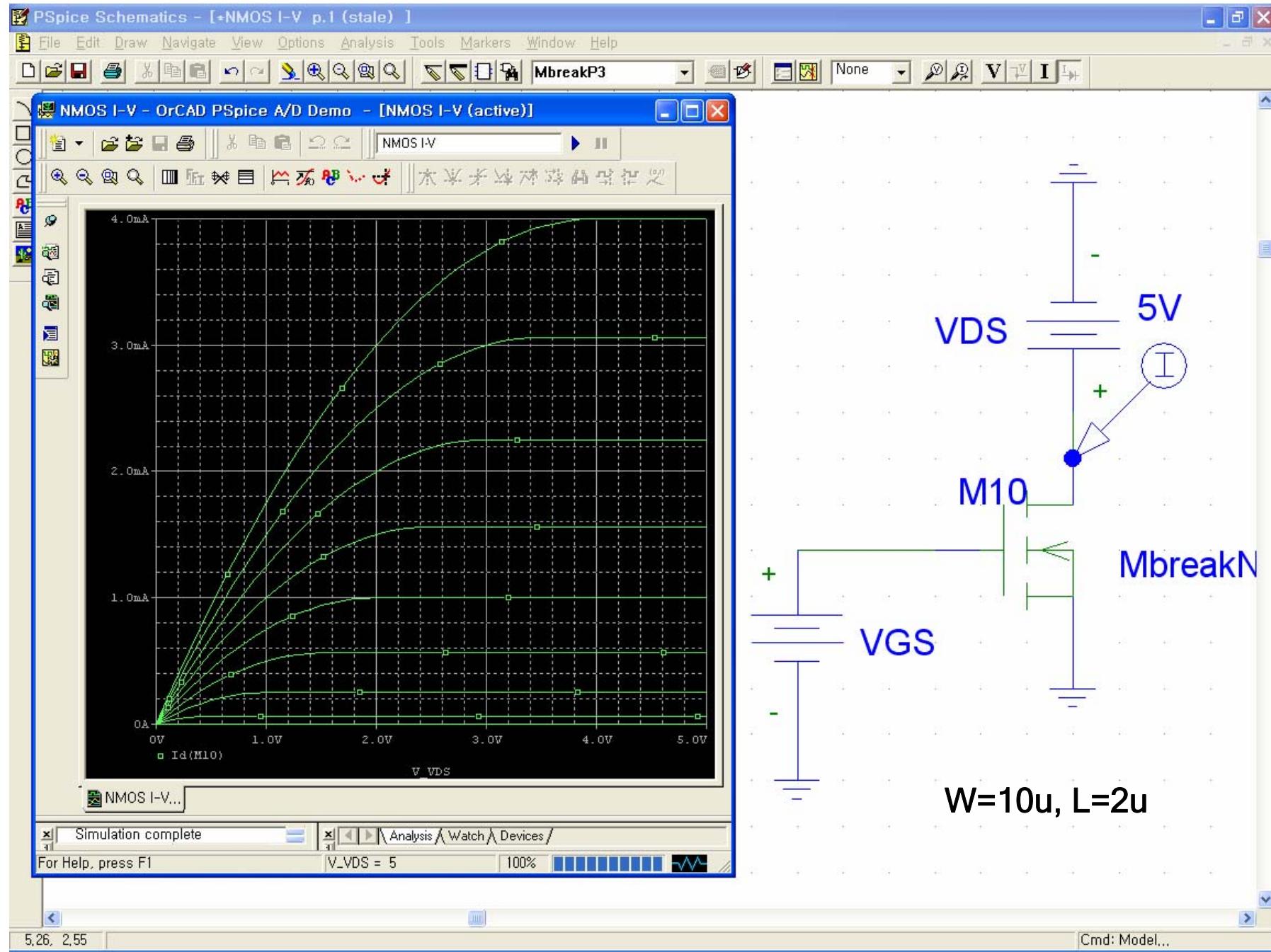
PSPICE simulation of NMOS

2. Set values for v_T , k ($=\mu_n C_{ox}$) in **Edit/Model/Edit Instance Model** after clicking NbreakN3.

```
.model MbreakN-X NMOS VTO=1, KP=1e-4
```

3. Set values for W and L by double clicking MbreakN3

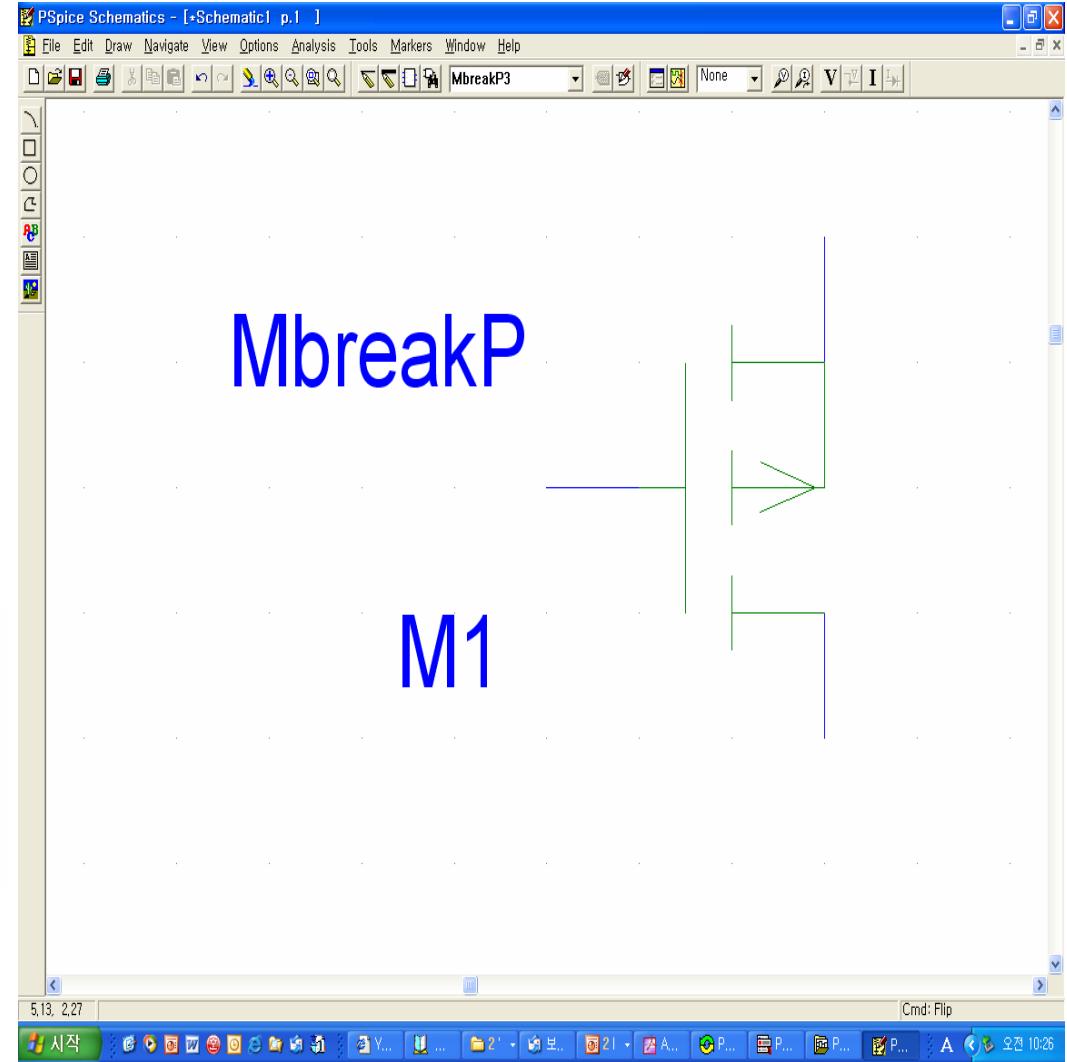
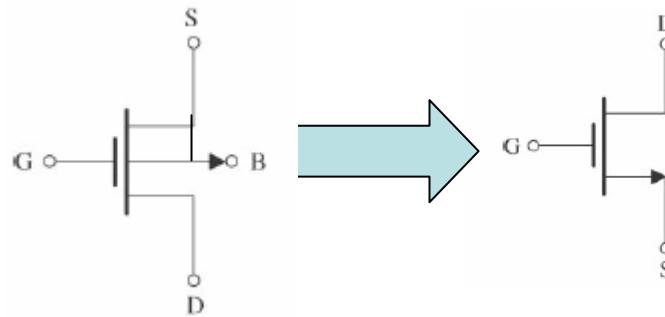
=> Simulate I-V characteristics of NMOS



Lect. 8: MOSFET Simulation

PSPICE simulation of PMOS

1. Use **MbreakP3** model in PSPICE
(S and B are tied)



Lect. 8: MOSFET Simulation

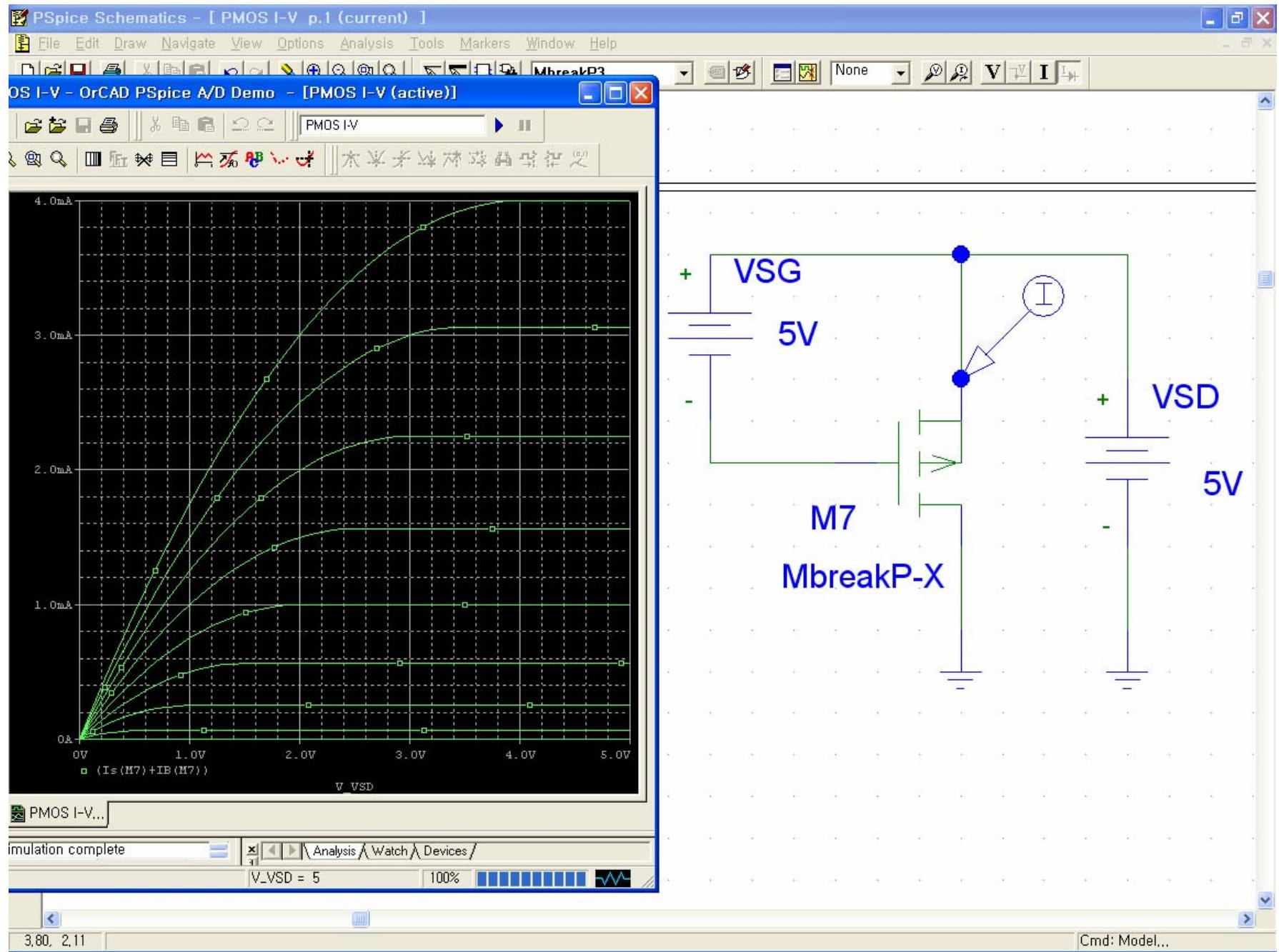
PSPICE simulation of PMOS

2. Set values for v_T , k ($=\mu_n C_{ox}$) in **Edit/Model/Edit Instance Model** after clicking MbreakP3.

.model MbreakP-X NMOS VTO=-1, KP=1e-4

3. Set values for W and L by double clicking MbreakP3

=> Simulate I-V characteristics of PMOS



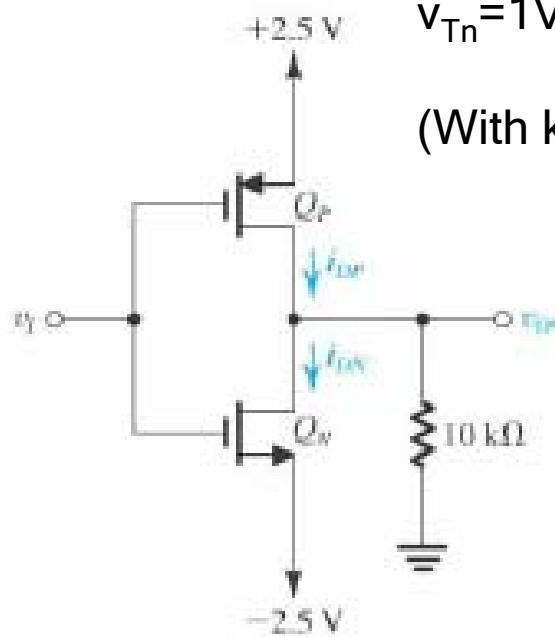
Lect. 8: MOSFET Simulation

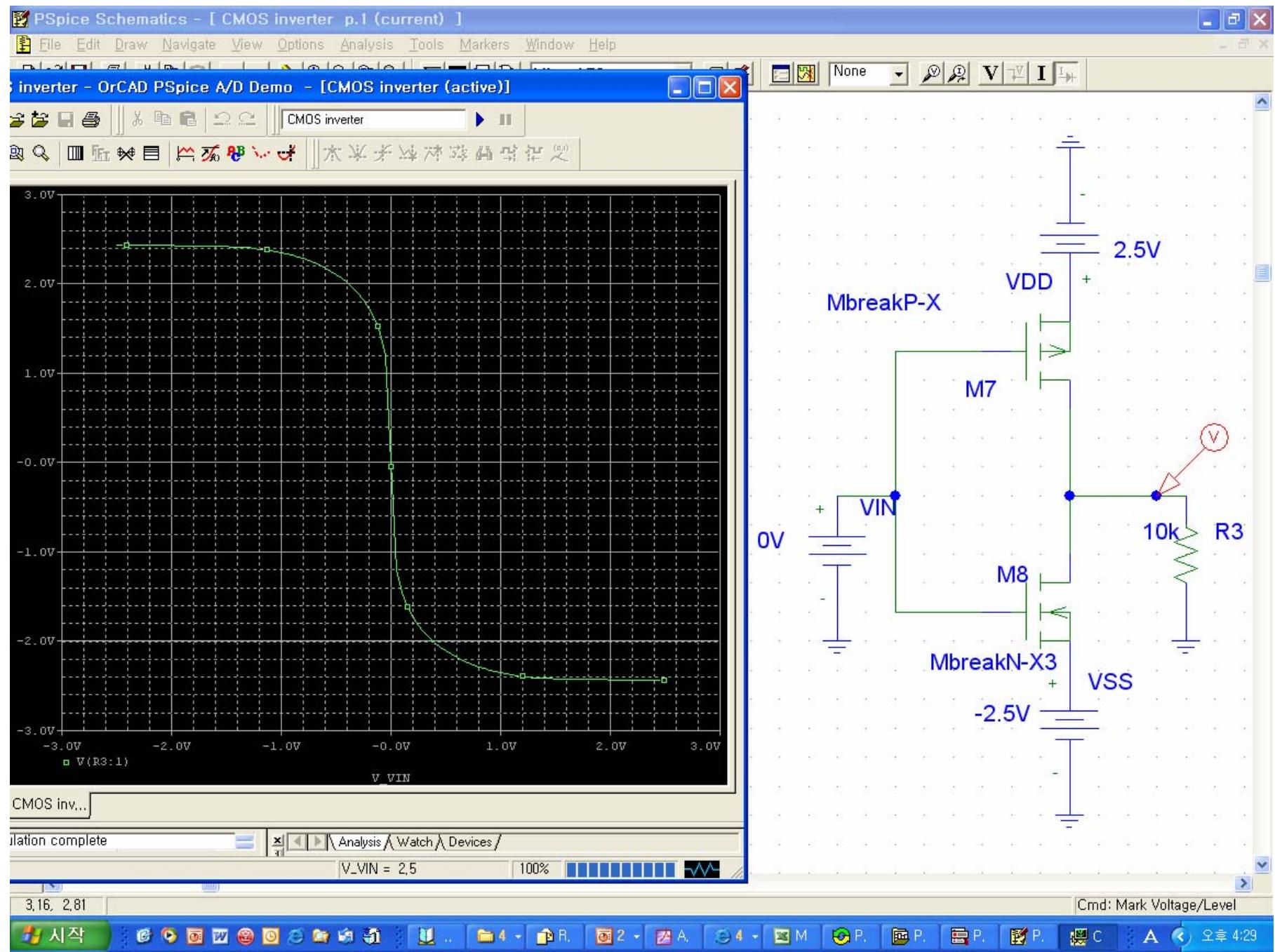
Example 4.7 (p. 269)

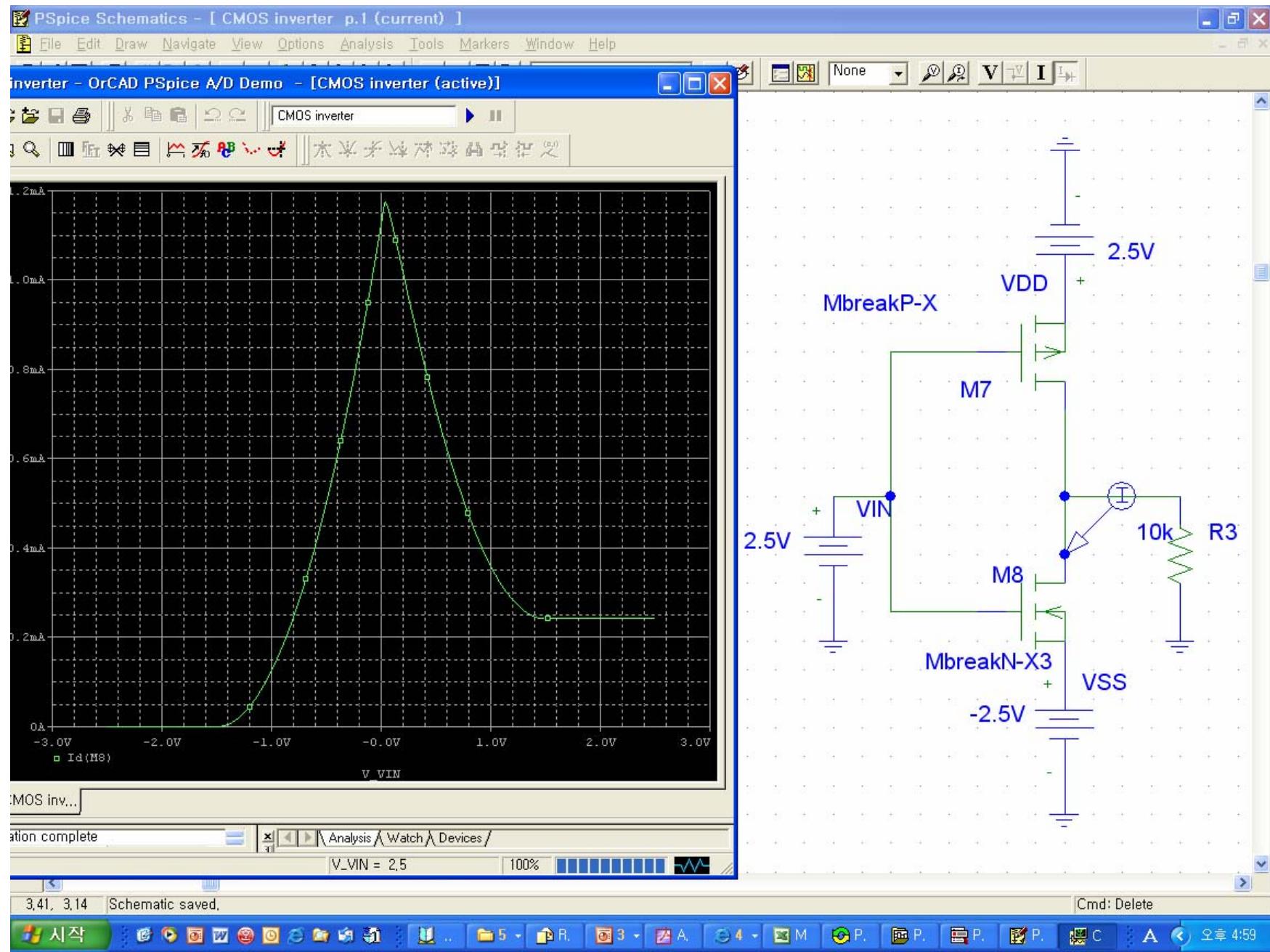
Determine i_{Dn} , i_{Dp} , v_o for $-2.5V < v_i = 2.5$ by PSPICE simulation.

$v_{Tn} = 1V$, $v_{Tp} = -1V$, both transistors have $k'(W/L) = 1mA/V^2$.

(With $k' = 1e-4 A/V^2$, $W/L = 10$)







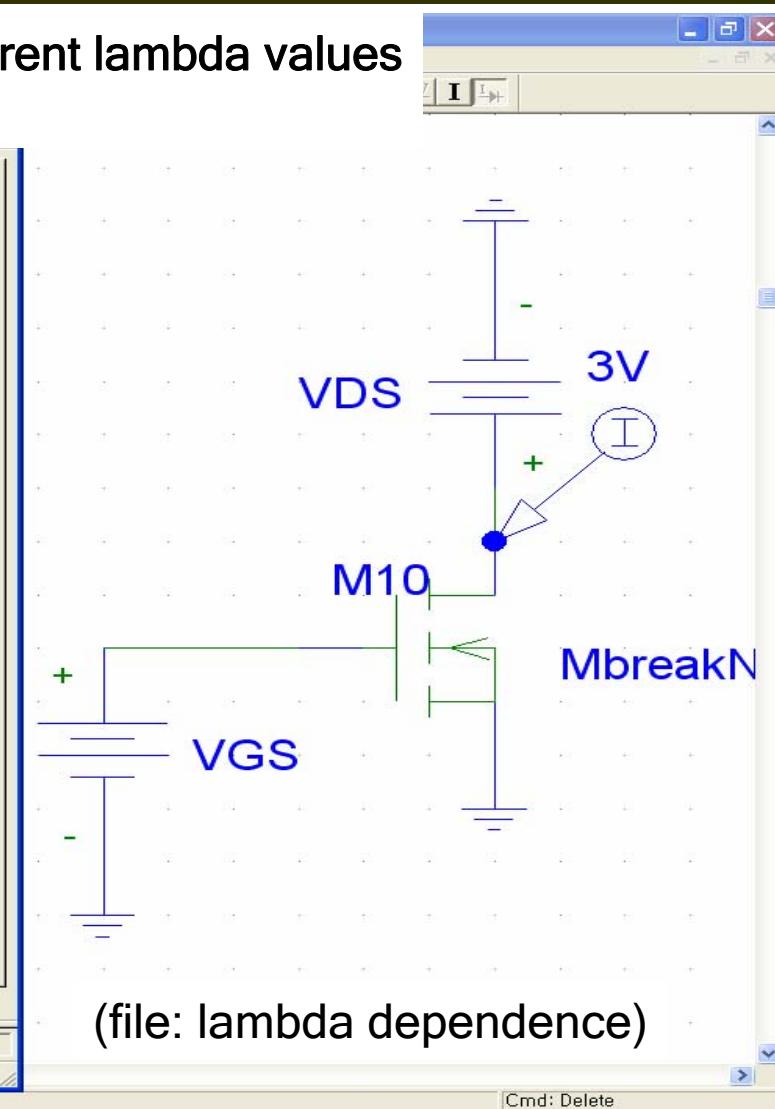
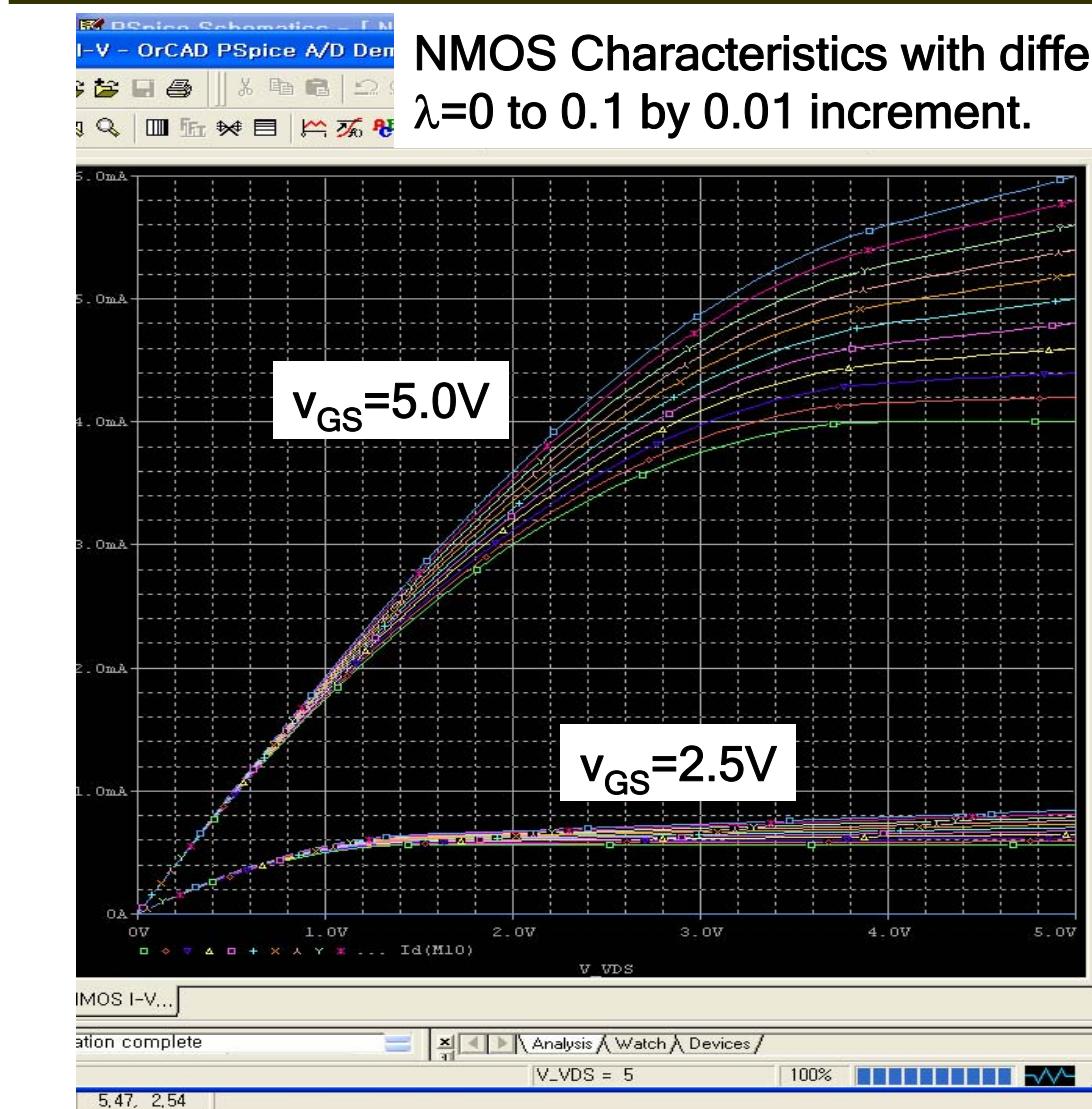
Lect. 8: MOSFET Simulation

- Modern transistors are very complicated in their structure.
Many parameters are needed to model their characteristics accurately in SPICE

An example of Advanced MOSFET models
(2 μ m double poly double metal technology)

```
.MODEL orbit2L2N NMOS LEVEL=2 PHI=0.700000 TOX=3.9800E-08 XJ=0.200000U TPG=1
+ VTO=0.8005 DELTA=4.2080E+00 LD=7.3840E-08 KP=6.6703E-05
+ UO=768.8 UEXP=1.1190E-01 UCRIT=7.3170E+03 RSH=3.8420E+00
+ GAMMA=0.5369 NSUB=6.5360E+15 NFS=9.2810E+10 VMAX=4.9600E+04
+ LAMBDA=3.2330E-02 CGDO=9.6098E-11 CGSO=9.6098E-11
+ CGBO=3.4582E-10 CJ=1.23000E-04 MJ=0.7500 CJSW=5.6800E-10
+ MJSW=0.26300 PB=0.6700000
* Weff = Wdrawn - Delta_W
* The suggested Delta_W is 2.0000E-09
```

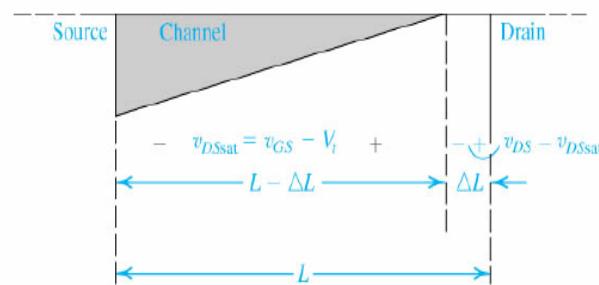
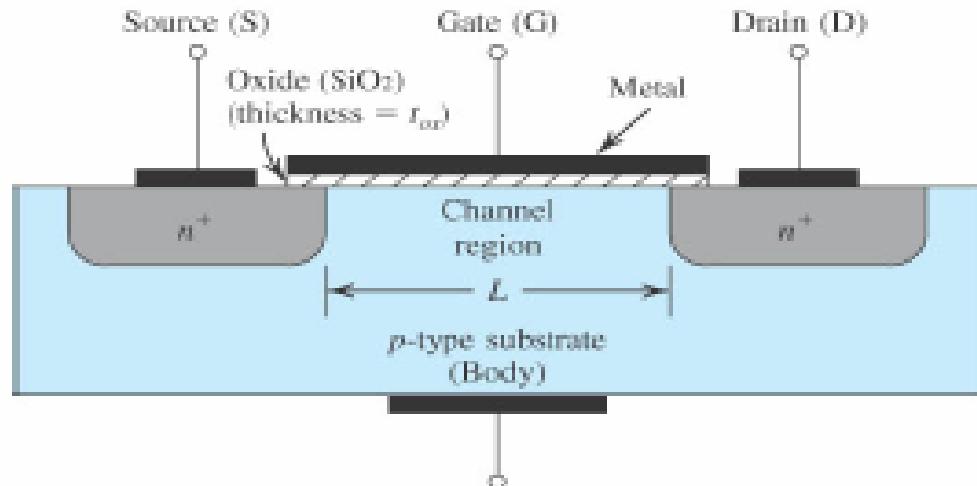
Lect. 8: MOSFET Simulation



(file: lambda dependence)

Lect. 8: MOSFET Simulation

Why? Channel length modulation



In saturation, v_{DS} increase causes reduction in actual channel length.

$$\begin{aligned} i_D &= \frac{1}{2} k' \frac{W}{L} (v_{GS} - V_t)^2 \\ &\Rightarrow \frac{1}{2} k' \frac{W}{L - \Delta L(v_{DS})} (v_{GS} - V_t)^2 \\ &= \frac{1}{2} k' \frac{W}{L(1 - \frac{\Delta L(v_{DS})}{L})} (v_{GS} - V_t)^2 \\ &\simeq \frac{1}{2} k' \frac{W}{L} (1 + \frac{\Delta L(v_{DS})}{L}) (v_{GS} - V_t)^2 \\ \text{Assuming } \frac{\Delta L(v_{DS})}{L} &= \lambda \cdot v_{DS} \\ i_D &= \frac{1}{2} k' \frac{W}{L} (1 + \lambda \cdot v_{DS}) (v_{GS} - V_t)^2 \end{aligned}$$

Lect. 8: MOSFET Simulation

Homework: Example 4.7 (p. 269)

Determine v_O for $-2.5V < v_I = 2.5$ by PSPICE simulation.

$v_{Tn}=1V$, $v_{Tp}=-1V$, both transistors have $k'(W/L)=1mA/V^2$.

(With $k'=1e-4 A/V^2$, $W/L=10$)

